

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

Claims 1-3 (canceled).

Claim 4 (currently amended): A magnetic recording medium comprising:  
a substrate;  
an underlying layer in which a large number of recesses of an extremely small size are uniformly demonstrated, the underlying layer being formed on the substrate; and  
an amorphous magnetic film is formed on the surface of the underlying layer in which the recesses of the extremely small size are demonstrated;

wherein the underlying layer is formed of tetraethoxysilane as a feedstock, and the underlying layer is a layer which is formed of silicon oxide and a mixture thereof and in which a large number of spherically-shaped voids of the same size are formed by removing spherically-shaped micelles which are self-arrayed in a face-centered cubic lattice configuration, wherein the surface of the underlying layer on which the amorphous magnetic film is deposited has been processed so that the recesses by voids are demonstrated uniformly; and

an amorphous magnetic film is formed on the surface of said underlying layer in which said recesses of the extremely small size are demonstrated.

wherein the amorphous magnetic film is layered on the recesses demonstrated in the underlying layer to form protuberances which are discrete with respect to one another.

Claims 5-7 (canceled).

Claim 8 (previously presented): The magnetic recording medium according to claim 4 wherein said underlying layer is a layer which is formed of silicon oxide and a mixture thereof and in which a large number of spherically-shaped voids of the same size, with the diameter of several nm to tens of nm, are formed uniformly to a face-centered cubic structure.

Claims 9-13 (canceled).

Claim 14 (currently amended): A magnetic recording medium comprising:

a substrate;

an underlying layer in which a large number of recesses of an extremely small size are uniformly demonstrated, the underlying layer being formed on the substrate; and

amorphous magnetic films are formed on the surface of the underlying layer in which the recesses of the extremely small size by the voids are demonstrated;

wherein the underlying layer is formed of tetraethoxysilane as a feedstock, and the underlying layer is a layer which is formed of silicon oxide and a mixture thereof and in which a large number of spherically-shaped voids of the same size are uniformly formed by removing spherically-shaped micelles which are self-arrayed in a face-centered cubic lattice configuration by F68 (EO<sub>77</sub>-PO<sub>29</sub>-EO<sub>77</sub>) or F108 (EO<sub>133</sub>-PO<sub>50</sub>-EO<sub>133</sub>) as a triblock copolymer, wherein the surface of the underlying layer on which the amorphous magnetic film is deposited has been processed so that the recesses by voids are demonstrated uniformly; and in which a large number of spherically-shaped voids of the same size are formed by removing spherically-shaped micelles which are self-arrayed in a face centered cubic lattice configuration; and

amorphous magnetic films are formed on the surface of the underlying layer in which said recesses of the extremely small size are demonstrated,

wherein the amorphous magnetic films are layered independently from one another on the each recesses demonstrated in the underlying layer to form protuberances which are discrete with respect to one another.